HIP

	Application No.	Applicant(s)	
Notice of Allowability	10/810,151	LIU ET AL.	
	Examiner	Art Unit	
	Anne M. Hines	2879	·
The MAILING DATE of this communication appe All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT Ri	ars on the cover sheet w. (OR REMAINS) CLOSED i or other appropriate comm GHTS. This application is	n this application. If not include unication will be mailed in due	ded course. THIS
1. This communication is responsive to <u>5/4/06</u> .			-
2. 🔀 The allowed claim(s) is/are <u>1-18</u> .			
 3.	been received. been received in Application to the communication to file ENT of this application. atted. Note the attached EX as reason(s) why the oath of the submitted. on's Patent Drawing Reviews Amendment / Comment of the submitted of the	on No ed in this national stage applicate a reply complying with the reply and the reply and the reply complying with the reply and the complete and the complete action of the drawings in the front (not the fre 1.121(d).	equirements NOTICE OF
Attachment(s) 1. Notice of References Cited (PTO-892) 2. Notice of Draftperson's Patent Drawing Review (PTO-948) 3. Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date 4. Examiner's Comment Regarding Requirement for Deposit of Biological Material	5. ☐ Notice of I 6. ☐ Interview S Paper No 8), 7. ☐ Examiner's	nformal Patent Application (P ⁻ Summary (PTO-413), ./Mail Date s Amendment/Comment s Statement of Reasons for Al	
	,		

Art Unit: 2879

DETAILED ACTION

Response to Amendment

The amendment filed on May 4, 2006, has been entered and acknowledged by the Examiner.

Claims 1-18 are pending in the instant application.

Allowable Subject Matter

Claims 1-18 are allowed.

Regarding independent claims 1 and 11, the references of the Prior Art of record fail to teach or suggest the combination of the limitations as set forth in claims 1 and 11, and specifically comprising the limitation wherein after providing an insulative layer with a first surface, depositing a catalyst on the first surface of the insulative layer, forming a spacer with a plurality of openings so that patterned areas of the catalyst is exposed in the openings, forming carbon nanotubes from the catalyst layer and forming cathode electrodes on top of the carbon nanotubes, gate electrodes are formed on a second opposite surface of the insulative layer offset from the patterned catalyst areas and portions of the insulative layer corresponding to the carbon nanotubes are removed.

Regarding claims 2-10, and 12-17, claims 2-10, and 12-17 are allowable for the reasons given in claims 1 and 11 because of their dependency status from claims 1 and 11.

Regarding independent claim 18, the references of the Prior Art of record fail to teach or suggest the combination of the limitations as set forth in claim 18, and

specifically comprising the limitation wherein after providing a catalyst layer, forming a barrier on the catalyst layer, forming carbon nanotubes beside the barrier layer on the catalyst layer and forming a cathode electrode on the carbon nanotubes with the cathode electrode supported by the barrier, the catalyst layer is removed and a gate electrode is provided under the carbon nanotubes.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Anne M. Hines whose telephone number is (571) 272-2285. The examiner can normally be reached on Monday through Friday from 8:00-4:30.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nimesh Patel can be reached on (571) 272-2457. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Anne M Hines Patent Examiner Art Unit 2879

MARICELI SANTIAGO PRIMARY EXAMINER